

## AMENDMENTS TO THE CLAIMS

Please cancel Claim 1, without prejudice or disclaimer of subject matter.

Please amend Claim 2, to read as follows.

1. (Canceled)

2. (Currently Amended) A method of manufacturing a substrate for an ink jet recording head, wherein said substrate has a supply port, penetrating said substrate, for supplying liquid and an energy generating element for generating energy for ejecting the liquid, said method comprising:

a step of forming a protecting film on a surface of said substrate which is opposite from a surface on which said energy generating element is disposed;

a step of etching a surface of said protecting film by liquid containing ammonium fluoride to make said protecting film a thin film;

a step of forming an etching-resistant film on the thus etched protecting film;

a step of forming opening patterns in said protecting film and said etching-resistant film;

a step of forming an opening as said supply port in said substrate by etching said substrate through said opening patterns;

a step of removing a projected end portion of said protecting film which is projected into said opening and which is produced in said opening forming step and which is projected into said opening formed in a side opposite from the side having said energy generating element; and

a step of removing said etching-resistant film after said projected end portion removing step.

3. (Original) A method according to Claim 2, wherein said substrate comprises silicon.

4. (Original) A method according to Claim 3, wherein said supply port forming step uses crystal anisotropic etching.

5. (Original) A method according to Claim 2, wherein said projected end removing step uses etching.

6. (Original) A method according to Claim 2, wherein said protecting film comprises silicon oxide.

7. (Original) A method according to Claim 2, wherein said etching-resistant film comprises polyetheramide.